Grating couplers in polymer with a thin Si$_3$N$_4$ layer embedded

Linghua Wang*,$a$,$b$,$d$, Yanlu Li$^a$,$d$, Marco Garcia Porcel$^{a,d}$, Diedrik Vermeulen$^{a,d}$, Xiuyou Han$^b$, Jinyan Wang$^c$, Xigao Jian$^c$, Mingshan Zhao$^b$ and Geert Morthier$^{a,d}$

$^a$Photonics Research Group, INTEC-Department, Ghent University-IMEC, Ghent B-9000, Belgium
$^b$School of Physics and Optoelectronic Technology, Dalian University of Technology, Dalian, 116023, China
$^c$Department of Polymer Science & Materials, Dalian University of Technology, Dalian, 116023, China
$^d$Center for Nano- and Biophotonics (NB-Photonics), Ghent University, Ghent B-9000, Belgium

ABSTRACT

Polymer has been considered to be an ideal material option for integrated photonics devices. To measure these devices, normally the route of horizontal coupling is chosen to couple the light into or out of the polymer waveguide. Due to the relatively low refractive index, implementing the surface grating coupler in this material system remains to be a challenge. In this paper, we present a polymer based surface grating coupler. Rather than expensive CMOS fabrication, the device is fabricated through a simple and fast UV based soft imprint technique utilizing self-developed low loss polymer material. The coupling efficiency is enhanced by embedding a thin Si$_3$N$_4$ layer between the waveguide core and under cladding layer. Around -19.8dB insertion loss from single-mode fiber (SMF) to single-mode fiber is obtained for a straight waveguide with grating coupler at each end. If collected with multi-mode fiber (MMF), it can be reduced to around -17.3dB. The 3dB bandwidth is 32nm centered at 1550nm. The proposed surface grating coupler and its easy fabrication method would be attractive for practical applications.

Keywords: polymer waveguide, surface grating coupler, inverted-rib waveguide, coupling efficiency

1. INTRODUCTION

Recently, biological and chemical sensors have attracted lots of attention due to their vast applications in the fields of food safety and environmental monitoring, point-of-care diagnostics, drug discovery and so on. Among these different types of sensors, planar integrated photonic biosensors own distinct advantages. By using photonic biosensors as transducer and detecting their output optical signal, label-free and real time monitoring of the dynamics of molecules’ reactions is made possible. The sensor can be designed as a planar cavity structure, a ring or disk resonator for example, to reduce the footprint but greatly enhance the sensitivity [1, 2]. Fabricating photonic biosensors with mature techniques such as CMOS based processes or novel nanoimprint lithography further reduces the chip cost with high volume production [3, 4].

Besides the advantages mentioned above, compact sized photonic biosensors with different functionalized surfaces can be accommodated onto a single chip, which makes multiplexed sensing possible. This has been realized within the SOI platform through the well known surface grating coupler [5]. The output signals from different channels during sensing are vertically coupled into free space and collected by an infrared camera. Besides the SOI platform, polymer has also been considered to be an ideal material platform for photonic biosensors, with the advantages such as extremely low cost, biocompatibility and so on [6, 7]. The polymer based photonic biosensors can perform as well as their counterparts in SOI with similar design structures [8-11]. However, a surface grating coupler is difficult to be implemented in this material platform because of the low refractive index contrast [12, 13], which limits the application of photonic biosensors based on polymer for multiplexed sensing. In contrast, the route of horizontal coupling is usually chosen in order to couple the light into or out of the polymer waveguide, in which case the requirement for good waveguide facets is high [14]. Another problem for horizontal coupling is small tolerance on the alignment. For single mode polymer waveguides, the measured power could fall dramatically with a few micrometers fiber drift. In order to circumvent these problems, we propose a grating coupler built on the polymer platform. Rather than expensive CMOS fabrication, the

* linghua.wang@intec.ugent.be; phone +32 - 9 - 264 3318; fax +32-9-264 3593;
device is fabricated through a simple UV based soft imprint technique utilizing self-developed low loss polymer material. The coupling efficiency is enhanced by embedding a thin Si$_3$N$_4$ layer between the waveguide core and under cladding layer. Around -19.8dB insertion loss (fiber to fiber) is obtained for a straight waveguide with grating couplers at each end. By calculation, the proposed grating coupler has a coupling efficiency of around 12%. The 3dB bandwidth is 32nm centered at 1550nm.

2. PROPOSED STRUCTURE AND SIMULATION

As mentioned before, the fundamental reason why the surface grating couplers cannot obtain a high coupling efficiency is the low refractive index of the polymer. The perturbation from the grating structures on the polymer waveguide surface has a limited influence on the waveguide mode, such that most of the light transmits directly through the waveguide instead of being diffracted out of the plane. Therefore the upward radiated power can be increased if this perturbation is strengthened. The field profile must also be optimized in order to increase the coupling to the fiber.

The proposed structure is depicted in Fig. 1. The grating pattern is fabricated on the under cladding layer, which sits on top of the Si substrate. A high refractive index layer, Si$_3$N$_4$ in our case, is selectively deposited on the grating and then embedded between the under cladding and waveguide core layer. The excess part of the Si$_3$N$_4$ layer is removed from the waveguide to prevent additional loss.

The simulation is carried out with the combination of CAMFR and FDTD (Finite-time-domain-difference). Parameters such as thickness of waveguide core, thickness of Si$_3$N$_4$ layer, grating height, grating period and so on are optimized to obtain suitable coupling angle, higher upward power, ideal diffracted field profile and thus higher coupling efficiency with the fiber. The electric field plot with and without the embedded high index Si$_3$N$_4$ layer are shown in Fig. 2. The used parameters are as follows: thickness of waveguide core $d=1.7\mu$m, grating height $e=0.7\mu$m, thickness of Si$_3$N$_4$ layer $t=0.2\mu$m, grating period $\lambda=1.7\mu$m. It can be clearly seen that after adding the Si$_3$N$_4$ layer, the perturbation of the surface grating on the waveguide mode is strongly enhanced, resulting in more upward power with diffraction angle around 43 degree. Besides that, the near field electric field starts exhibiting a quasi Gaussian profile, which is more easily fitted to the field profile of the fiber to have higher coupling efficiency. This is shown in Fig. 3. The spectral response of the grating with the optimized structure is shown in Fig. 4. It shows a maximum coupling efficiency with the single mode fiber of around 19%. Another benefit brought by this structure is polarization selectivity. The TM mode light cannot be coupled into or out of the polymer waveguide as effective as the TE mode light, and only has an efficiency of less than 6%.

Fig. 1 The proposed polymer based surface grating coupler

Fig. 2 The electric field plot without (a) and with (b) the embedded high index Si$_3$N$_4$ layer
We develop lithography a waveguide a n optical prop low viscosity this work me with low refr. The process...and dry etching method, this technique has been proved to be an efficient way to directly pattern the polymer waveguide and devices. However, this process has certain requirements on the imprinted material. Besides the good optical properties such as low optical loss, low birefringence and high thermal stability, good UV curing property and low viscosity are needed to make it well compatible with the UV based soft imprint technique. The material we used for this work meets the requirements above. Its two components, PSQ-LH with high refractive index (n=1.52) and PSQ-LL with low refractive index (n=1.45), are used as the waveguide core and cladding respectively [15, 16].

The process starts with the fabrication of the patterned mold. The PDMS soft mold is replicated from a master mold on which the grating and waveguide patterns are defined by the contact lithography. The obtained soft mold is then pressed against the under cladding layer which is spin coated on the silicon wafer. After 3min UV light curing with a intensity of

3. MATERIALS AND FABRICATION PROCESSES

We developed a simple UV based soft imprint technique to realize the structure proposed above. Compared with the lithography and dry etching method, this technique has been proved to be an efficient way to directly pattern the polymer waveguide and devices. However, this process has certain requirements on the imprinted material. Besides the good optical properties such as low optical loss, low birefringence and high thermal stability, good UV curing property and low viscosity are needed to make it well compatible with the UV based soft imprint technique. The material we used for this work meets the requirements above. Its two components, PSQ-LH with high refractive index (n=1.52) and PSQ-LL with low refractive index (n=1.45), are used as the waveguide core and cladding respectively [15, 16].
around 2000 mJ/cm², the soft mold is peeled from the substrate, leaving the grating and waveguide patterns on the under cladding layer. 2 hours of 180°C thermal curing is used to fully cure this layer. In order to realize the selectively Si₃N₄ embedded structure, at first the previously obtained sample is deposited with Si₃N₄ through PECVD. This step needs to be optimized because our polymer cannot resist too high temperature (above 200°C) during deposition. While using too low temperature will be detrimental to this dielectric layer, especially its refractive index will drop dramatically. By experimenting, the deposition temperature was chosen to be 150°C. Around 17 min time was used to achieve the targeted 200 nm layer thickness. Rather than dry etching, a simple wet etching method was used to completely remove the Si₃N₄ layer out of the waveguide region, leaving only the grating area covered by the Si₃N₄. After the spin coating and curing of the core layer PSQ-LH, the proposed surface grating coupler structure was realized. The fabrication process is shown in Fig. 5. The microscope and SEM images are shown in Fig. 6a and Fig. 6b.

![Fabrication Process Diagram](image1)

**Fig. 5** The fabricating process of UV soft imprint lithography combined with wet etching to realize the proposed structure.

![Microscope and SEM Images](image2)

**Fig. 6** The microscope (a) and SEM (b) picture of the fabricated surface grating coupler with Si₃N₄ layer imbedded between the core and under cladding layer.
4. MEASUREMENT RESULTS

The straight waveguide with two surface grating couplers at each end is measured with vertical setup. A cleaved single mode fiber connected to a tunable laser through the polarization controller was used to launch the light. The light diffracted by the surface grating coupler at the output was collected by a single-mode fiber (SMF) or a multi-mode fiber (MMF), which is connected to a power meter. The measurements result is shown in Fig. 7. The optimal coupling angle was found to be 40°. Under this measuring angle, around -19.8dB insertion loss (SMF to SMF) is obtained. We measured the straight waveguide loss with the similar inverted-rib structure through Fabry-Perot resonance method before and it was found to be 1.7dB/cm. In this case the length of the straight and tapered waveguide connected two surface grating couplers is 5mm, resulting in an estimated transmitting loss of 0.85dB. The link loss is measured to be 0.42dB at 1550nm wavelength. Thus the coupling efficiency for each surface grating coupler can be determined to be -9.27dB (nearly 12%) conservatively. There are another two factors we still haven’t taken into account because they are difficult to be predicted currently. One is the junction loss from the grating coupler to the waveguide and the other is the surface reflection loss. Considering this, the resulting coupling efficiency can be even higher. The 3dB bandwidth is 32nm centered at 1550nm. MMF was also used to receive the output power. Because of the large aperture of the MMF, the total insertion loss (SMF to MMF) was reduced by 2.5dB, which is -17.3dB.

![Fig. 7 The measured fiber to fiber transmission of the straight waveguide with two grating couplers at each end.](image)

In order to find out that how the energy is distributed within the first order of the proposed surface grating coupler, we carefully tune the angle of the output SMF while keeping that of the input SMF at 40°. The measured result is shown in Fig. 8. The 3dB angle bandwidth is around 7°. This result confirms that the first order is the main order of such grating coupler. The small energy distributed angle also shows the possibility of imaging the output light onto an infrared camera in the far field.
5. CONCLUSION

In this paper, a surface grating coupler based on polymer platform is proposed. A high refractive index layer of Si₃N₄ is embedded between the under cladding and waveguide layer to obtain good directionality and higher coupling efficiency with the fiber. Rather than expensive CMOS fabrication, the device is fabricated through a simple UV based soft imprint technique utilizing self-developed low loss polymer material. Around 12% of the coupling efficiency with the single mode fiber is obtained. The 3dB bandwidth centered at 1550nm is 32nm. The proposed structure would be very attractive in the applications where out of plane coupling or multiplexed signal processing is needed.

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